Report

"XEPMA analysis of the samples received from Proton21 laboratory"

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Summary

Sample description. The samples (accumulating screens numbered 7550 and 7203) represent copper disks each approximately 1.2 cm in diameter with a hole in the middle. As a result of the target explosion, the target material is deposited at the surface of the screen in the general form of radial rays pointing away from the target position. The microphotographs presented with the samples allow identifying the spots for analysis.

Aim of the analysis. To confirm the results by Proton21 regarding the presence of elements different from the principal components of target material and accumulating screen material in the provided samples.

Device description. The scanning electron microscopy was performed on a Philips ESEM XL 30, equipped with energy dispersive X-ray spectroscopy (EDS), EDAX DX-4. The microphotographs were taken with a backscattering detector. The EDS x-ray spectra were used for element identifications and element normalized quantifications.

Measurement parameters. The microscope was used in its high-vacuum mode. The acceleration voltage of 30 kV was used for all spots. The measurement parameters of interest are presented at the bottom of each microphotograph.

General remarks. The aim of this analysis was to verify the results obtained by Proton21 regarding the elemental composition of foreign inclusions deposited on the surface of the accumulating screen after the explosion of the target. As the surfaces of the samples presented for the analysis is highly non-uniform, with the elemental composition of the inclusions drastically varying from spot to spot, the verification procedure was chosen as follows.

- 1. Proton21 presents the microphotographs of the samples with the selected spots clearly marked for the analysis, alongside with the spectra obtained at these spots
- 2. We find the marked spots and take spectra. To ensure consistency we present the microphotographs of the samples with the spots we took for analysis (also clearly marked at the photographs), alongside with our spectra taken at these spots.

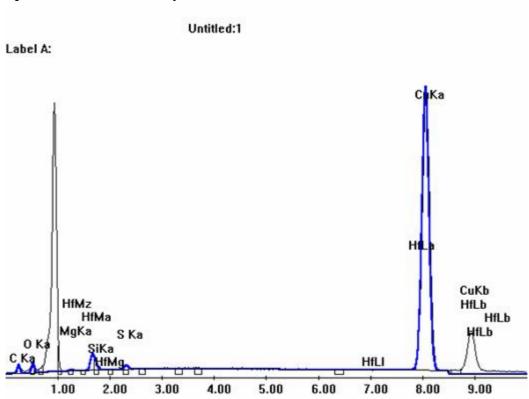
The spectra and microphotographs by Proton21 allowed clear identification of the analysis points. The "spot analysis" mode (not "area analysis" mode) was used to ensure stronger signal from non-uniform inclusions.

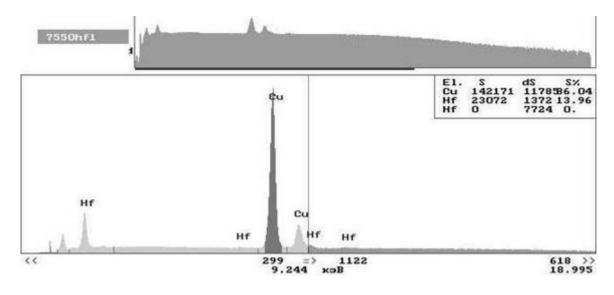
Overall conclusion. We were able to identify most of the elements that were registered by Proton21, therefore confirming the presence of foreign inclusions at the surface of the accumulating screen that differ from the declared composition of the screen and the target materials. The discrepancies between some of the spectra supplied by Proton 21 and the corresponding spectra from this analysis may be explained by slight shifting the observation point. However we were able to show the presence of foreign inclusions roughly of the same elemental composition as in the original spectra. Also, because of the above error in locus determination the concentrations of elements found in this analysis may differ from the ones presented in the Proton21 spectra.

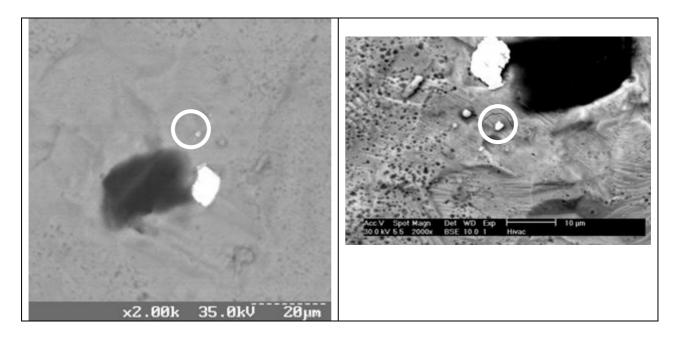
Results of the analysis: Sample 7550

Point 7550hf1 (t4).

Spectrum from this analysis:







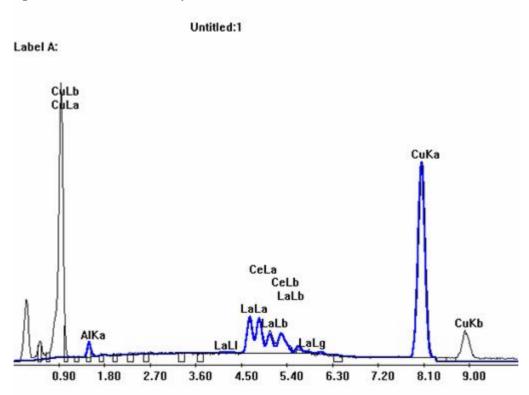
Quantitative analysis:

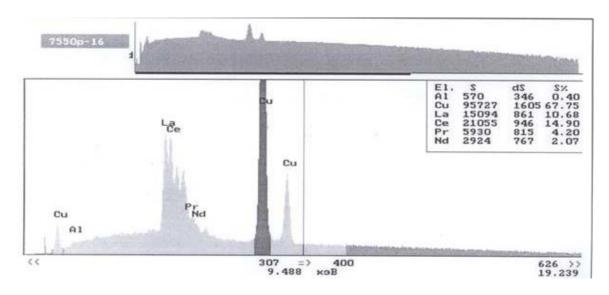
	F Quantifi Normalize		andardless	s)				
Element	Wt %	At %	K-Ratio	Z	A	F		
СК	6.63	24.91	0.0102	1.1624	0.1317	1.0004	: !	
O K	3.37	9.52	0.0092	1.1457	0.2360	1.0033		
MgK	0.60	1.11	0.0008	1.1036	0.1158	1.0001		
SiK	0.69	1.11	0.0017	1.1041	0.2213	1.0001		
SK	0.54	0.75	0.0023	1.0966	0.3967	1.0000		
HfL	0.00	0.00	0.0000	0.8373	1.1045	1.0000		
CuK	88.17	62.60	0.8630	0.9748	1.0041	1.0000	` ;	
Total	100.00	100.00						

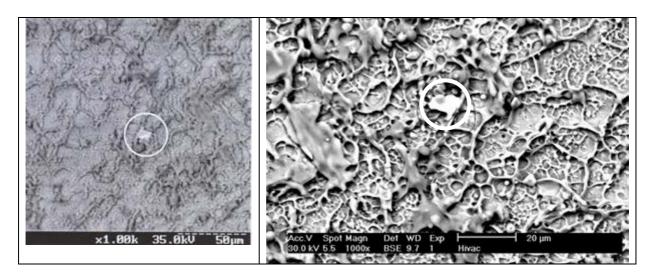
Comment. We were able to identify trace amounts of **Hf**, although much less than in the original spectrum supplied by Proton21.

Point 7550p16

Spectrum from this analysis:





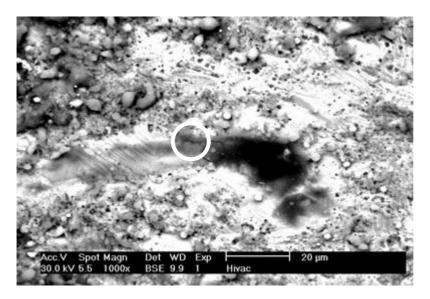


Quantitative analysis:

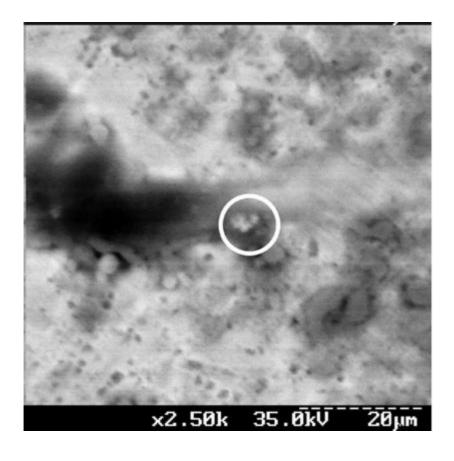
Comment. We may confidently register Al, La and Ce. We could not with the same level of confidence register Nd and Pr.

Point 7550t1

Microphotograph from this analysis



At this point we found out that the particle marked for analysis was not present at the sample surface, as it has possibly fallen off during shipment (compare to the original picture below). Therefore, no spectra were taken.

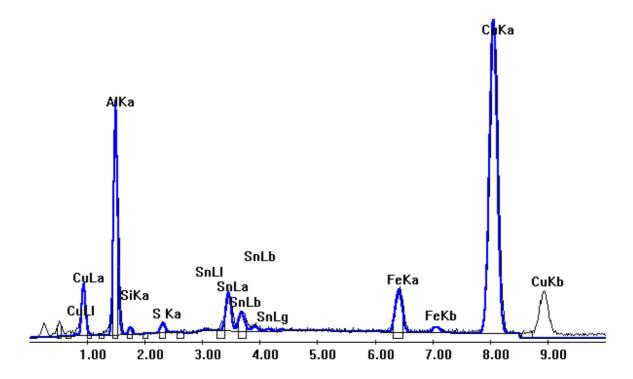


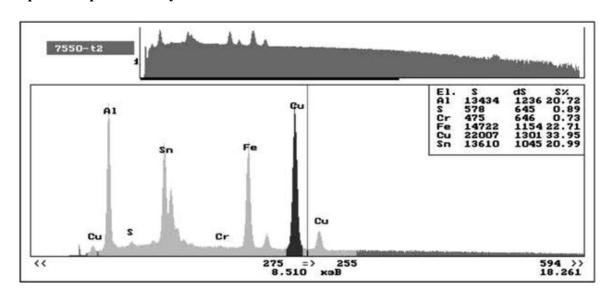
Point 7550t2.

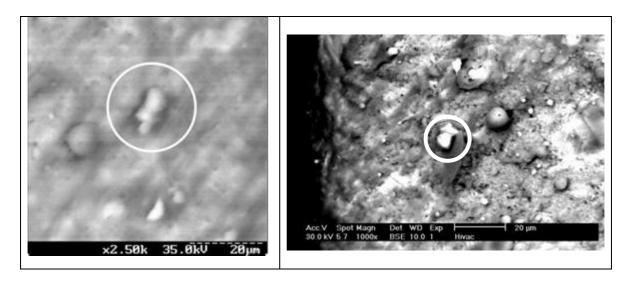
Spectrum from this analysis:

Untitled:1

Label A:





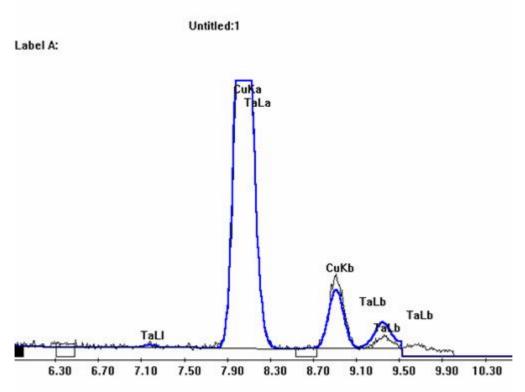


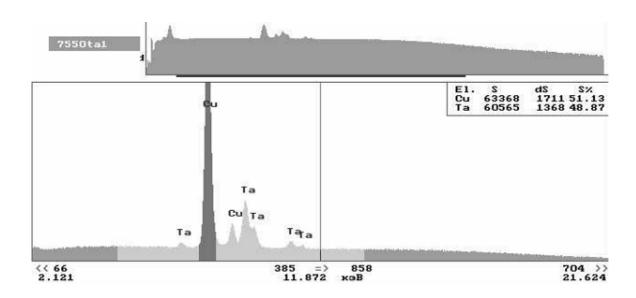
Quantitative analysis:

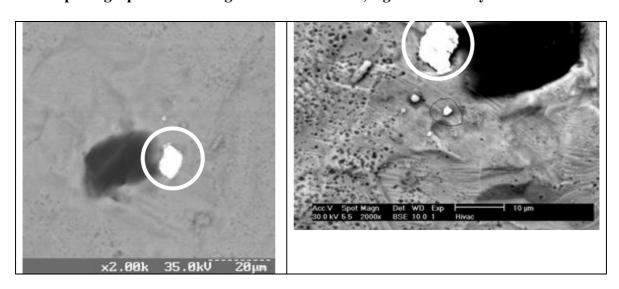
	F Quantifi Normalize		andardless	s)				, * .
Element	Wt %	At %	K-Ratio	Z	Α	F		
AlK	28.60	48.77	0.0631	1.0665	0.2066	1.0007		
SiK	0.94	1.54	0.0021	1.0984	0.2062	1.0009		
S K	0.83	1.19	0.0034	1.0910	0.3699	1.0022		
SnL	6.99	2.71	0.0538	0.8653	0.8879	1.0017		1
FeK	4.30	3.54	0.0466	0.9943	0.9501	1.1474		
CuK	58.34	42.24	0.5519	0.9687	0.9766	1.0000	+ 3	
Total	100.00	100.00						

Comment: We confidently register Al, Sn, Fe, S, Si. We cannot confidently identify Cr.

7550t3 (ta1). Spectrum from this analysis:







Quantitative analysis:

EDAX ZAF Quantification (Standardless) Element Normalized

Element	Wt %	At %	K-Ratio	Z	Α	F	_
SiK	37.09	61.31	0.1406	1.0859	0.3492	1.0000	
CuK	47.57	34.76	0.4480	0.9601	0.9808	1.0000	
TaL	15.34	3.94	0.1361	0.8231	1.0778	1.0000	
Total	100.00	100.00					

Element	Net Inte.	Bkgd Inte.	Inte. Error	P/B
CuL	146.12	3.44	0.76	42.44
SiK	266.23	5.26	0.56	50.62
CuK	264.10	4.87	0.56	54.20
TaL	33.48	4.82	1.68	6.95

Comment. Ta is confidently registered

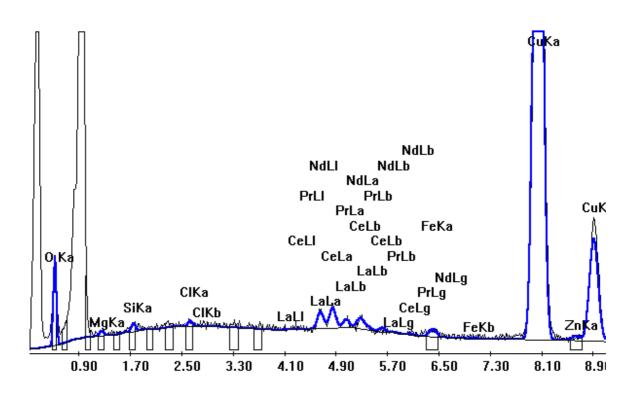
Results of the analysis: Sample 7203

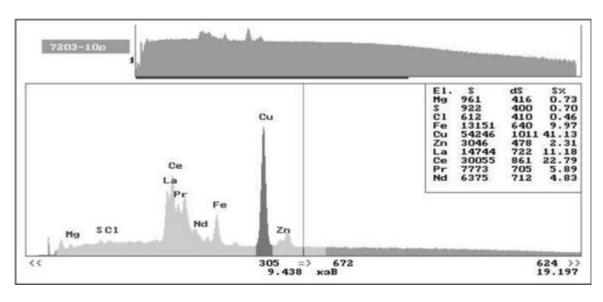
Point 7203P10

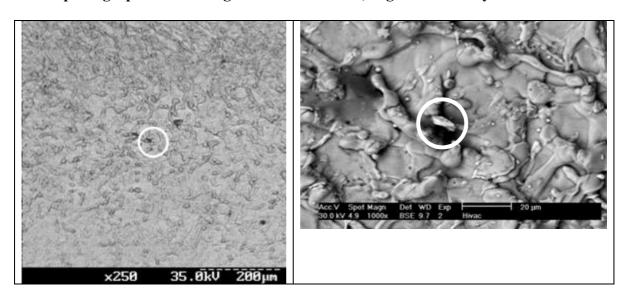
Spectrum from this analysis:

Untitled:1

Label A:







Quantitative analysis:

EDAX ZAF Quantification (Standardless) Element Normalized

Element	Wt %	At %	K-Ratio	Z	Α	F
O K MgK SiK ClK LaL CeL PrL NdL FeK CuK ZnK	6.60 0.61 0.57 0.22 1.75 2.19 0.00 0.37 87.11 0.58 100.00	21.95 1.33 1.09 0.34 0.67 0.83 0.00 0.00 0.35 72.97 0.47	0.0202 0.0008 0.0014 0.0012 0.0175 0.0226 0.0000 0.0000 0.0045 0.8518 0.0057	1.1591 1.1164 1.1168 1.0621 0.8745 0.8835 0.8947 0.8895 1.0129 0.9876 0.9911	0.2631 0.1120 0.2119 0.4855 1.0685 1.0798 1.0889 1.0962 0.9605 0.9902	1.0029 1.0001 1.0002 1.0009 1.0706 1.0853 1.1026 1.1233 1.2501 1.0000
10041	100.00					

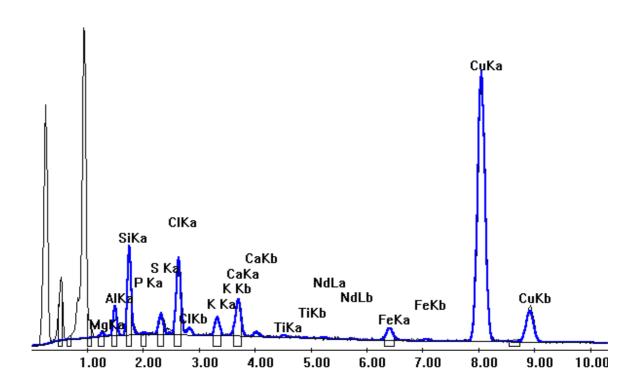
Comments: We confidently identify Mg, Si, La, Ce, Cl, Zn, Fe, O. We could not identify Nd and Pr.

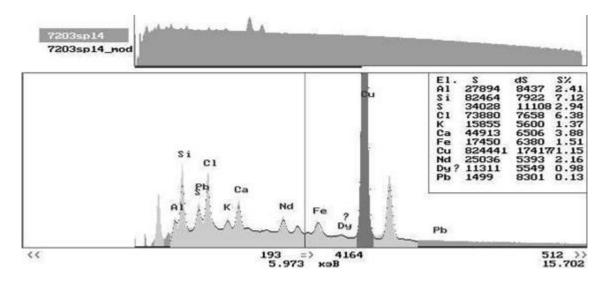
Point 7203p14

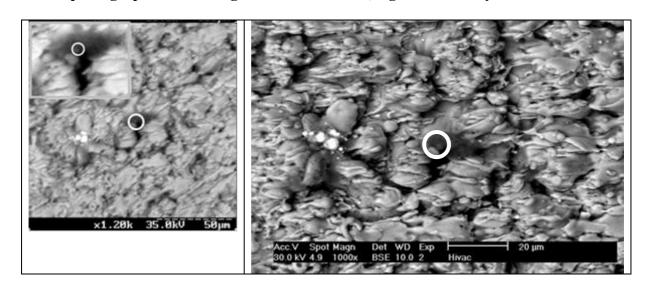
Spectrum from this analysis:

Untitled:1

Label A:







Quantitative analysis:

EDAX ZAF Quantification (Standardless) Element Normalized

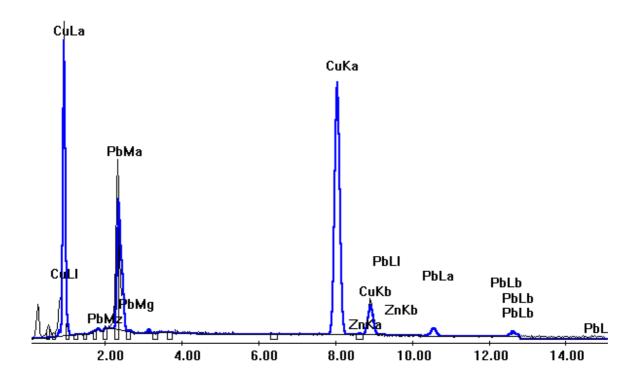
Element	Wt %	At %	K-Ratio	Z	A	F
мак	1.15	2.23	0.0018	1.0883	0.1430	1.0026
AlK	4.91	8.56	0.0102	1.0572	0.1964	1.0037
SiK	12.14	20.34	0.0338	1.0888	0.2554	1.0024
PK	0.19	0.29	0.0006	1.0535	0.2968	1.0041
SK	2.22	3.26	0.0095	1.0815	0.3919	1.0054
ClK	7.32	9.72	0.0368	1.0357	0.4835	1.0027
KK	1.57	1.89	0.0107	1.0516	0.6372	1.0130
CaK	3.18	3.74	0.0247	1.0754	0.7108	1.0150
Tik	0.23	0.23	0.0019	0.9816	0.8208	1.0361
NdL	0.25	0.08	0.0025	0.8655	1.0483	1.0831
FeK	1.55	1.31	0.0171	0.9854	0.9519	1.1747
CuK	65.28	48.35	0.6167	0.9597	0.9843	1.0000
Total	100.00	100.00			1555 D. 7565 C	

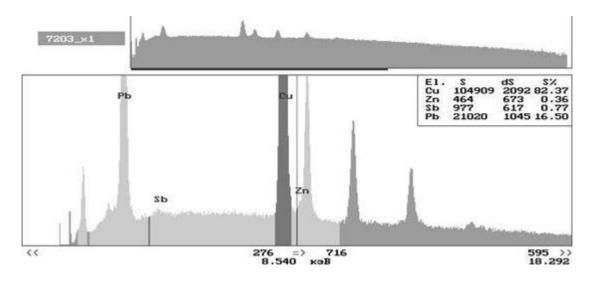
Point 7203x1

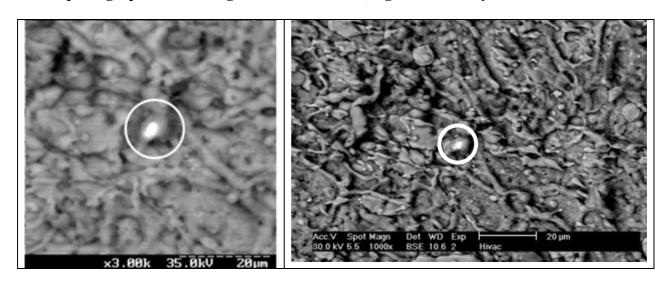
Spectrum from this analysis:

Untitled:1

Label A:







Quantitative analysis:

EDAX ZAF Quantification (Standardless) Element Normalized

Element	Wt %	At %	K-Ratio	Z	Α	F	
ZnK PbL	0.51	0.55 4.88	0.8574 0.0052 0.1133	1.0221	0.9855	1.0167	

Element	Net Inte.	Bkgd Inte.	Inte. Error	P/B
CuL	290.92	3.08	0.73	94.59
PbM	168.44	13.00	0.98	12.96
CuK	523.92	10.48	0.54	49.97
ZnK	2.77	10.61	16.24	0.26
PbL	18.26	6.74	3.37	2.71

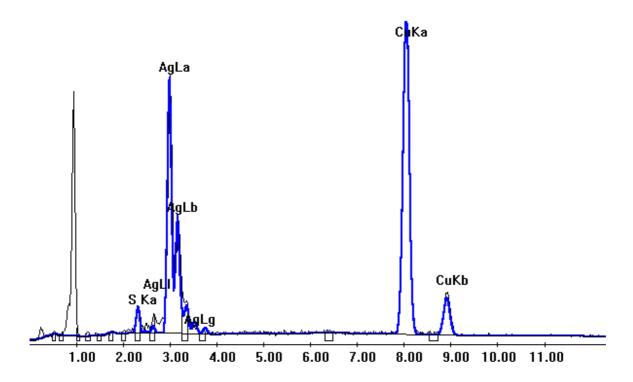
Comment. We may confidently register **Zn** and **Pb**. We could not with the same level of confidence register **Sb**.

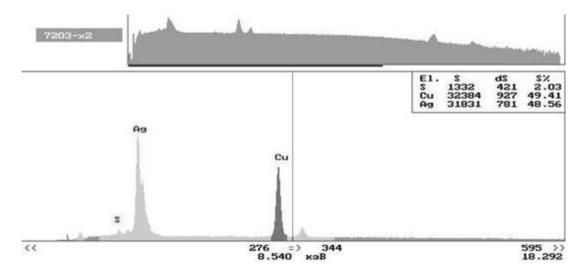
Point 7203x2

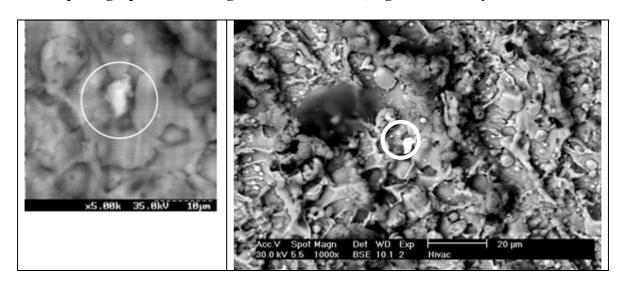
Spectrum from this analysis:

Untitled:1

Label A:







Quantitative analysis:

EDAX ZAF Quantification (Standardless) Element Normalized

Element	Wt %	At %	K-Ratio	Z	Α	F	
			0.0095 0.3110				
			0.5723				
Total	100.00	100.00					

Element	Net Inte.	Bkgd Inte.	Inte. Error	P/B	
S K AgL CuK	18.25 192.93 362.15	5.92 6.51 8.18	2.77 0.75 0.55	3.08 29.63 44.26	

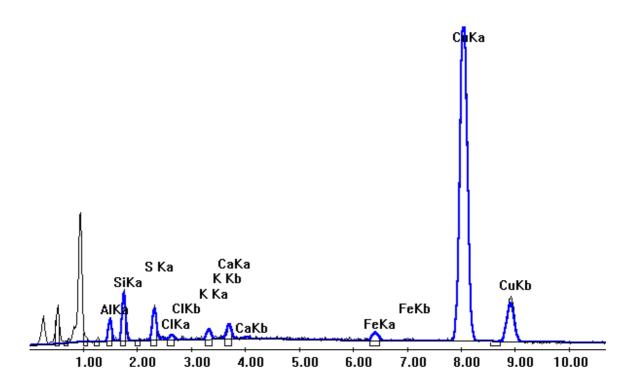
Comment. We confidently register Ag and S.

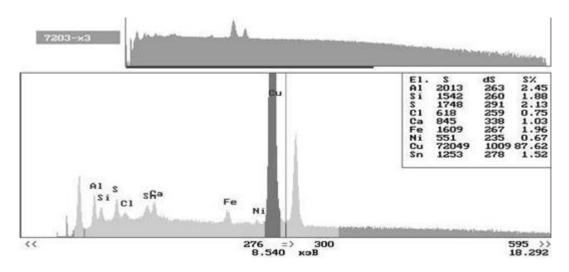
Point 7203x3

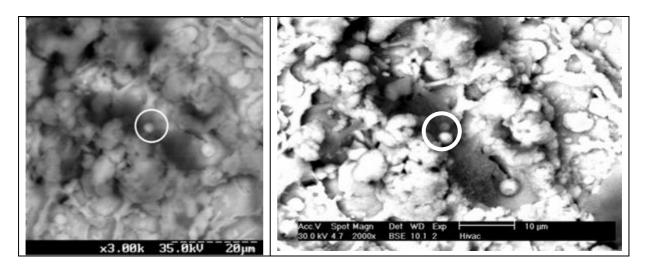
Spectrum from this analysis:

Untitled:1

Label A:







Quantitative analysis:

EDAX ZAF Quantification (Standa	ardless)
Flement Normalized	

Eleme	nt Wt %	At %	K-Ratio	, Z	Α	F	_
Al	.K 4.39	8.57	0.0081	1.0727	0.1719	1.0019	
Si	.K 7.54	14.13	0.0189	1.1047	0.2266	1.0011	
S	K 3.59	5.88	0.0148	1.0972	0.3756	1.0010	
Cl	.K 0.53	0.79	0.0026	1.0507	0.4591	1.0012	
K	K 0.81	1.10	0.0058	1.0699	0.6545	1.0131	
Ca	K 1.20	1.57	0.0098	1.0939	0.7316	1.0190	
Fe	K 1.01	0.95	0.0121	1.0010	0.9654	1.2422	
Cu	K 80.92	67.01	0.7839	0.9754	0.9931	1.0000	
Tota	1 100.00	100.00					

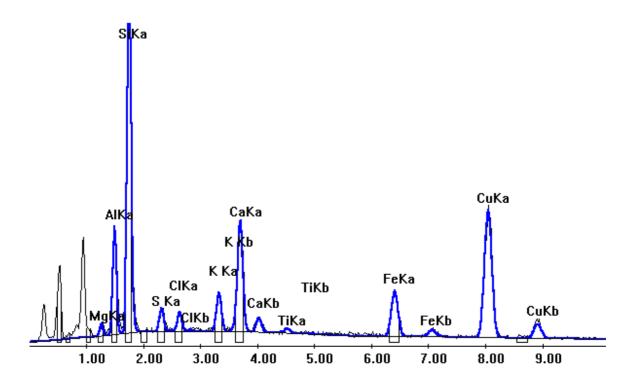
Comment. We may confidently register Al, Si, S, Cl, K, Ca, Fe. We could not with the same level of confidence register Ni and Sn.

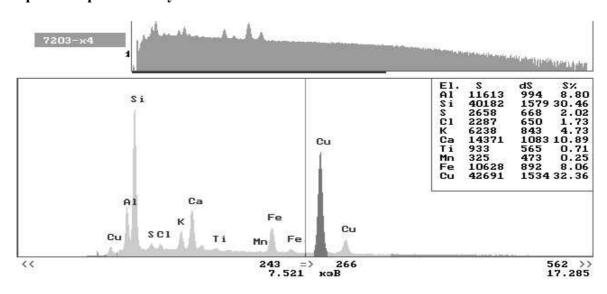
Point 7203x4

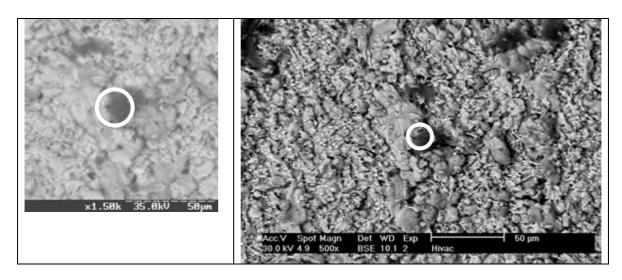
Spectrum from this analysis:

Untitled:1

Label A:







Quantitative analysis:

EDAX ZAF Quantification (Standardless) Element Normalized

Element	Wt %	At %	K-Ratio	Z	Α	F
MgK AlK SiK S K ClK K K CaK TiK FeK CuK	1.57 10.24 37.12 2.39 1.75 3.01 8.90 0.49 5.80 28.74	2.35 13.77 47.97 2.71 1.79 2.79 8.06 0.37 3.77 16.42	0.0038 0.0330 0.1388 0.0093 0.0080 0.0198 0.0654 0.0037 0.0547 0.2551	1.0450 1.0152 1.0456 1.0388 0.9949 1.0030 1.0260 0.9388 0.9435 0.9177	0.2311 0.3138 0.3567 0.3705 0.4591 0.6464 0.7098 0.7897 0.9379 0.9673	1.0082 1.0116 1.0024 1.0049 1.0066 1.0160 1.0087 1.0191 1.0662 1.0000
Total	100.00	100.00				

Comment. We may confidently register Mg, Al, Si, S, Cl, K, Ca, Ti and Fe. We could not with the same level of confidence register Mn.